



HIGH ENERGY PICOSECOND LASER MODULE

GENKI XP



NEW



SWISS MADE

NEW 100W MICROMACHINING PICOSECOND LASER

The Genki XP platform pushes industrialization of high energy and high power **picosecond** lasers further. The system is based on the ultra-stable Genki seed laser and provides clean pulses shorter than **10 ps**, which is an optimal pulse duration window for many micromachining applications. To satisfy the increasing demand of picosecond laser workstations, the Genki XP has been optimized to provide up to **100 W** of average power and **300 µJ** pulse energy at the industry-standard wavelengths of **1030 and 1064 nm**. The laser can be tailored to work at lower repetition rates with even higher energies or at several MHz to follow high-speed automated processes. The Genki XP has been designed for the easiest and most cost-effective possible system integration can be mounted in any direction and offers full remote control capability.

OPTIONS:

- + Green 532 nm
- + UVA 355 nm
- + UVC 266 nm
- + Synchronization to external clock

MAIN APPLICATIONS:

- + Material processing
- + Glass and sapphire cutting
- + Plasma generation
- + Nonlinear optics

OUTSTANDING FEATURES :

- + Pulse energy up to 300 µJ
- + High pulse quality
- + Narrow spectral width
- + Excellent energy and pointing stability
- + Mountable in any direction
- + Maintenance free – no alignment required
- + Complete remote control
- + Burst mode
- + 24/ 7 operation



Specifications subject to change without notice, May 2017

ISO 9001 : 2008

ISO 13485 : 2012

	GENKI - 10 XP	GENKI - 10 XPC
CENTER WAVELENGTH	1064 nm	1030 nm
PULSE DURATION ^{1,2}	< 10 ps	< 10 ps
AVG. OUTPUT POWER [UP TO]²	100 W	40 W
PULSE ENERGY [UP TO]²	300 μ J	100 μ J
PULSE REPETITION RATE ^{1,2}	single shot – 80 MHz	
SPECTRAL BANDWIDTH ²	< 1 nm	< 2 nm
BEAM QUALITY	$M^2 < 1.3$, TEM ₀₀	
PER	> 20 dB	
AMPLITUDE NOISE [24 H]	< 1% rms	< 2% rms
LASER OUTPUT		collimated free space
ENVIRONMENTAL		
WARM-UP TIME	< 30 minutes	
OPERATION TEMPERATURE	18 °C – 32 °C	
STORAGE TEMPERATURE	- 20 °C – 65 °C	
ON/OFF CYCLES	> 10000	
MECHANICAL		
SIZE LASER SYSTEM	505 x 630 x 142 mm ³	300 x 401 x 81 mm ³
WEIGHT SYSTEM	70 kg	15 kg
SIZE CONTROL UNIT	-	133 x 483 x 400 mm ³ (19"/3U rack mount)
WEIGHT CONTROL UNIT	-	10 kg
ELECTRICAL		
POWER SUPPLY	24 VDC/25 A + 48 VDC/21 A or 90 – 264 VAC, 47 – 63 Hz	24 VDC/25 A or 90 – 264 VAC, 47 – 63 Hz
POWER CONSUMPTION	1600 W	600 W
COOLING		
LASER SYSTEM	water cooled	

¹ Please inquire for possible combinations of pulse duration, average power and repetition rate

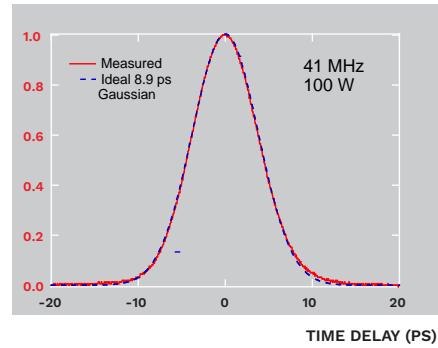
² Spectral bandwidth depends on pulse duration, pulse energy and repetition rate

³ Exact size and weight depend on pulse duration, pulse repetition rate, average power and wavelength



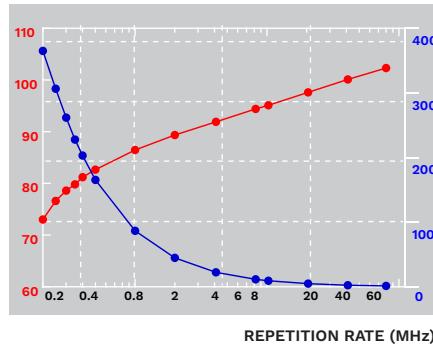
PULSE PROFILE

AUTOCORRELATION SIGNAL



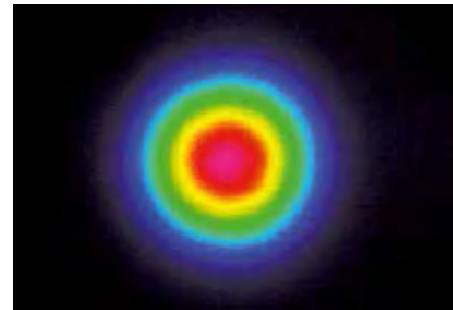
OUTPUT POWER AND PULSE ENERGY

AVERAGE POWER (W)

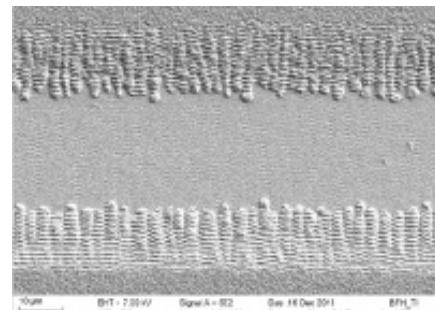


PULSE ENERGY (μ J)

BEAM PROFILE



APPLICATION



P2 scribe on Mo/CIGS/IZO thin film solar module
realized with the Genki XP, 4W, 10 kHz, 1064 nm.
© A. Burn et al., Proc. SPIE 9735, 973504-1:13, 2016

China: Eachwave scientific instrument Co., Ltd
Tel: +86-21-62209657, +86-21-54843093
Email: sales@eachwave.com
Web: www.eachwave.com

Onefive GmbH | Althardstrasse 70 | CH-8105 Regensdorf | Switzerland |
Tel. +41 43 5383657 | contactus@onefive.com | www.onefive.com